PROCEEDINGS OF SPIE

Pacific Rim Laser Damage 2013

Optical Materials for High Power Lasers

Jianda Shao
Takahisa Jitsuno
Wolfgang Rudolph
Editors

19–22 May 2013
Shanghai, China

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Published by
SPIE

Volume 8786

Proceedings of SPIE 0277-786X, V. 8786

SPIE is an international society advancing an interdisciplinary approach to the science and application of light.

Pacific Rim Laser Damage 2013: Optical Materials for High Power Lasers,
edited by Jianda Shao, Takahisa Jitsuno, Wolfgang Rudolph, Proc. of SPIE Vol. 8786,
878601 · © 2013 SPIE · CCC code: 0277-786X/13/$18 · doi: 10.1117/12.2030524

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Author(s), "Title of Paper," in *Pacific Rim Laser Damage 2013: Optical Materials for High Power Lasers*, edited by Jianda Shao, Takahisa Jitsuno, Wolfgang Rudolph, Proceedings of SPIE Vol. 8786 (SPIE, Bellingham, WA, 2013) Article CID Number.

ISSN: 0277-786X
ISBN: 9780819496027

Published by
SPIE
P.O. Box 10, Bellingham, Washington 98227-0010 USA
Telephone +1 360 676 3290 (Pacific Time) · Fax +1 360 647 1445
SPIE.org

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